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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/008,253	11/09/2001	Gian Francesco Lorusso	KLA1P035	2556
22434 7	7590 06/17/2003			
BEYER WEAVER & THOMAS LLP			EXAMINER	
P.O. BOX 778 BERKELEY, G	CA 94704-0778		GURZO, PAUL M	
			ART UNIT	PAPER NUMBER
			2881	
			DATE MAILED: 06/17/2003	;

Please find below and/or attached an Office communication concerning this application or proceeding.

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		Application No.	Applicant(s)		
Office Action Summary		10/008,253	LORUSSO ET AL.		
		Examiner	Art Unit		
		Paul Gurzo	2881		
Period fo	The MAILING DATE of this communication Reply	on appears on the cover sheet w	ith the correspondence address		
THE I - External from the control of	ORTENED STATUTORY PERIOD FOR IT MAILING DATE OF THIS COMMUNICAT asions of time may be available under the provisions of 37 sold (6) MONTHS from the mailing date of this communicate period for reply specified above is less than thirty (30) day a period for reply is specified above, the maximum statutory re to reply within the set or extended period for reply will, by reply received by the Office later than three months after the patent term adjustment. See 37 CFR 1.704(b).	ION. CFR 1.136(a). In no event, however, may a ion. s, a reply within the statutory minimum of thin period will apply and will expire SIX (6) MOI y statute, cause the application to become A	reply be timely filed ty (30) days will be considered timely. ITHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).		
1)[Responsive to communication(s) filed o	n <u>02 June 2003</u> .			
2a) ⊡	This action is FINAL . 2b)	This action is non-final.			
3) 🗌	Since this application is in condition for closed in accordance with the practice uson of Claims				
•	Claim(s) <u>1-20,22 and 23</u> is/are pending	in the application.			
4a) Of the above claim(s) is/are withdrawn from consideration.					
5) Claim(s) is/are allowed.					
′	Claim(s) <u>1-20,22 and 23</u> is/are rejected.				
·	Claim(s) is/are objected to.				
·	Claim(s) are subject to restriction	and/or election requirement.			
, ,	ion Papers	·			
9)	The specification is objected to by the Ex	aminer.			
10)	The drawing(s) filed on is/are: a)□	accepted or b) objected to by	the Examiner.		
	Applicant may not request that any objection	n to the drawing(s) be held in abey	ance. See 37 CFR 1.85(a).		
11)	The proposed drawing correction filed on	is: a) approved b) c	disapproved by the Examiner.		
If approved, corrected drawings are required in reply to this Office action.					
12) The oath or declaration is objected to by the Examiner.					
Priority (ınder 35 U.S.C. §§ 119 and 120				
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).					
a) ☐ All b) ☐ Some * c) ☐ None of:					
1. Certified copies of the priority documents have been received.					
2. Certified copies of the priority documents have been received in Application No					
* (3. Copies of the certified copies of th application from the Internation See the attached detailed Office action for	nal Bureau (PCT Rule 17.2(a)).			
14) 🗌 A	Acknowledgment is made of a claim for do	omestic priority under 35 U.S.C.	§ 119(e) (to a provisional application).		
) The translation of the foreign langua Acknowledgment is made of a claim for de	- .			
Attachmen	it(s)				
2) Notice	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-9 mation Disclosure Statement(s) (PTO-1449) Paper	48) 5) Notice of	Summary (PTO-413) Paper No(s) Informal Patent Application (PTO-152)		
S Patent and T	rademark Office				

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DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-6,10-12, 17-20, and 22-23 are rejected under 35 U.S.C. 102(b) as being anticipated by Iwasaki (4,983,830).

Regarding claims 1,2,10,11, Iwasaki teaches a method for inspecting a specimen by detecting electrons that scatter comprising the steps of scanning and directing the electron beam (1) for irradiation (col. 1, lines 46-55 and fig. 2), setting a filter at a first and second voltage level, detecting the scattered electrons at both voltage levels, and determining the differential intensity levels (col. 3, lines 43-50, col. 4, lines 31-35, and claim 1). He further teaches the ability to repeat these steps and to generate an image of the specimen (col. 4, lines 1-6). It is inherent that the voltage levels are can be set to at successively higher and/or lower increments up to the level of the electron beam.

Regarding claim 3, Iwasaki teaches that the scattered electrons are secondary electrons (col. 2, lines 50-61), and it is inherent that the voltage levels encompass an energy spectrum so that the secondary electrons are detected.

Regarding claims 4-6, Isawaki teaches the detection of desired secondary electrons, and it is inherent that he sets the voltage to the desired levels so that selective detection occurs (col. 3,

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lines 43-50), and he teaches measuring the potential of the surface of an integrated circuit (col. 2, lines 59-61), which is a doped semiconductor wafer.

Regarding claim 12, Iwasaki teaches a method for inspecting a specimen by detecting electrons that scatter comprising the steps of scanning and directing the electron beam (1) for irradiation (col. 1, lines 46-55), setting a filter at a first and second voltage level, detecting the scattered electrons at both voltage levels, and determining the differential intensity levels (col. 3, lines 43-50, col. 4, lines 31-35, and claim 1). He further teaches the ability to repeat these steps and to generate an image of the specimen (col. 4, lines 1-6). It is inherent that the voltage levels are can be set to at successively higher and/or lower increments up to the level of the electron beam. Further, the image that is determined from the different voltages (col. 2, lines 28-37 and col. 4, lines 1-6) can easily be found at numerous times during the detection.

Regarding claim 17, Iwasaki teaches that the scattered electrons are secondary electrons (col. 2, lines 50-61), and it is inherent that the voltage levels encompass an energy spectrum so that the secondary electrons are detected.

Regarding claims 18 and 19, Isawaki teaches the detection of desired secondary electrons, and it is inherent that he sets the voltage to the desired levels so that selective detection occurs (col. 3, lines 43-50), and he teaches measuring the potential of the surface of an integrated circuit (col. 2, lines 59-61), which is a doped semiconductor wafer.

Regarding claim 20, Iwasaki teaches a method for inspecting a specimen by detecting electrons that scatter comprising the steps of scanning and directing the electron beam (1) for irradiation (col. 1, lines 46-55), setting a filter at a first and second voltage level, detecting the scattered electrons at both voltage levels, and determining the differential intensity levels (col. 3,

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lines 43-50, col. 4, lines 31-35, and claim 1). He further teaches the ability to repeat these steps and to generate an image of the specimen (col. 4, lines 1-6). It is inherent that the voltage levels are can be set to at successively higher and/or lower increments up to the level of the electron beam. He teaches the use of a control computer system that is arranged to set the filter to the appropriate voltage levels (col. 1, line 65 - col. 2, line 2).

Regarding claims 22 and 23, Isawaki teaches that the ion beam apparatus is equipped with a secondary electron energy filter, which discriminates secondary electrons generated by the irradiation of an ion beam based on their energy levels (col. 4, lines 31-35). Further, it is inherent that the intensity levels correspond to the number of scattered electrons and voltages levels can be predetermined.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 7-9 and 13-16 are rejected under 35 U.S.C. 103(a) as being unpatentable over Iwasaki (4,983,830), and further in view of Lo et al. (6,344,750).

Regarding claim 7, Iwasaki teaches a method for inspecting a specimen by detecting electrons that scatter comprising the steps of scanning and directing the electron beam (1) for irradiation (col. 1, lines 46-55), setting a filter at a first and second voltage level, detecting the scattered electrons at both voltage levels, and determining the differential intensity levels (col. 3, lines 43-50, col. 4, lines 31-35, and claim 1). He further teaches the ability to repeat these steps

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and to generate an image of the specimen (col. 4, lines 1-6). It is inherent that the voltage levels are can be set to at successively higher and/or lower increments up to the level of the electron beam.

Iwasaki does not explicitly teach scanning a first and second material on the specimen, but Lo et al. teach scanning a first and second area (col. 4, lines 33-46), which can obviously mean an area on the same specimen, or an area on a different specimen. Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to scan multiple areas/materials so that comparison of the acquired images will identify defects in the patterned substrate.

Regarding claims 8 and 9, Iwasaki teaches the generation of an image as described above and that the scattered electrons are secondary electrons (col. 2, lines 50-61), and it is obvious that the voltage levels encompass an energy spectrum so that the secondary electrons are detected.

Regarding claims 13-15, Lo et al. teach a real-time control computer (92) having a real-time operating system (col. 8, lines 36-47, and Fig. 2). This real-time operating system means that the images are continuously generated and that the voltage application and energy determination is performed simultaneously.

Regarding claim 16, Lo et al. teach the use of scanning two different areas as described above.

Response to Arguments

Applicant's arguments filed on June 2, 2003 have been fully considered but they are not persuasive. Applicant argues that the prior art does not teach determining a differential electron intensity level, which is the difference between the first and second electron intensity levels.

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However, Iwasaki explicitly teaches an energy filtering means being disposed between the specimen and the detecting means for discriminating the secondary electrons emitted by the irradiated specimen according to their energy levels (claim 1). It is the position of the Examiner that this teaching of discriminating secondary electrons based on energy levels teaches on the claimed first and second energy levels and it is inherent that discrimination can only occur based on the determined intensity levels.

Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Paul Gurzo whose telephone number is (703) 306-0532. The examiner can normally be reached on M-Thurs. 7:30 - 6:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John Lee can be reached on (703) 308-4116. The fax phone numbers for the

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organization where this application or proceeding is assigned are (703) 872-9318 for regular communications and (703) 872-9319 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

PMG

June 11, 2003